

COPOLYESTER AND ITS MANUFACTURING METHOD

Patent Number: JP2001192441
Publication date: 2001-07-17
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Requested Patent: JP2001192441
Application Number: JP20000005277 20000105
Priority Number(s):
IPC Classification: C08G63/692; C08G63/688; C08G63/86
EC Classification:
Equivalents:

Abstract

PROBLEM TO BE SOLVED: To provide a copolyester and its manufacturing method suitable for a container or the like having gas barrier property, having high molecular weight and excellent in impact resistance, good in transparency and low in generation of a cyclic oligomer.

SOLUTION: This copolyester comprises acid components comprising isophthalic acid, terephthalic acid and an alkali metal salt of 5-sulfoisophthalic acid or an alkali earth metal salt of 5-sulfoisophthalic acid, and their mole ratio satisfies a specific formula and ethylene glycol and including copolymerized phosphorus compounds in amount of 1×10^{-4} - 200×10^{-4} mole per mole of the acid components, and the solution haze of the copolyester is $\leq 15\%$ and number average molecular weight $\geq 10,000$.

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